${\sf NIVERSITET}$ https://www.umu.se/en/research/infrastructure/nanolab/

NanoLab

we offer courses and trainings on demand

equipment are always leady to operate

permanent access and individual assistance

clean room class 100 (ISO5)

Filmetrics

Filmetrics F10-RT-UVX

Thin film measurements system based on spectral reflectance (SR). Suitable mostly for transparent films, enabling measurements of films 30 Å to 100 μm thick films.



Plasma Processing Diener ATTO & PE-100

> For varieties of surface treatment, such as: cleaning, surface activation, etching. Samples can be up to 20 cm in diameter, two/four inlet gases are available.



Metallization PVD75 Kurt J. Lasker evaporator

For producing metallic or organic thin layers between 1-400 nm at high vacuum pressure 5x10-8 Torr. The system has three deposition sources and one low temperature organic deposition source. Samples can be up to 30 cm in diameter, substrate rotation and heating up to 350°C and two gas inlets are available.



CLEAN ROOM

Controlled environment used in manufacturing or scientific research, with a low level of environmental pollutants such as airborne microbes, aerosol particles, dust, and chemical vapors.

WHY CLEAN ROOM

substances.

particle count.

Class 1 / ISO 3

Class 10 / ISO 4

Class 100 / ISO 5

Manufacture products require specific

limitation of concentration of airborne

contaminants. It is used for pharmaceuticals.

electronics, medical devices and chemical

CLEAN ROOM CLASIFICATION

Clean rooms are rated for purity according to

guidelines established in Federal Standard 209D and

ISO standard 14644. Air cleanliness is specified in

terms of the number of foreign particles per cubic foot of air, relating different combinations of particle size and

Class 1,000 / ISO 6 : 1,000 particles per cubic foot

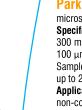
Class 10,000 / ISO 7 : 10,000 particles per cubic foot. Class 100,000 / ISO 8 : 100,000 particles per cubic foot

Class 100,000 / ISO 8: 1,000,000 particles per cubic foot

[particles measure 0.5 micron or less in diameter]

: only 1 particle per cubic foot

: 10 particles per cubic foot : 100 particles per cubic foot



Optical tensiometer

Optical Lithography

Microscopy

Nanoimprinter

Atomic force microscope

Park NX-Hivac AFM High vacuum atomic force microscope, offers greater accuracy, better repeatability. Specification: Vacuum level: E10-5 torr, Vacuum chamber: 300 mm x 420 mm x 320 mm, XYZ scanner: X-Y 100 µm x 100 μm and Z 15 μm , Sample stage size: 50 mm x 50 mm, Sample size: up to 150 mm x 150 mm, Sample thickness: up to 20 mm.

Applications: Surface imaging and topography (by contact, non-contact tapping. PinPoint, force modulation modes). Nanomechanical and Electrical properties, Nanolithography.



Attension Theta

Used for highly accurate measurements of static and dynamic contact angle, measure surface free energy, surface and interfacial tension.



Karl Süss Mask Aligner MJB3 used for photo lithography using 350 W mercury lamp and Suss diffraction-

reducing exposure optics. The primary exposure wavelengths of



365 or 403 nm lead to about 5 μ m minimum resolution. Olympus BX51 & GX71 provide high contrast, high



magnification, optimal color fidelity, Imaging in different modes and with different magnifications.



Obducat NIL 2.5 Nanoimprinter used to stamp a pattern into a polymer coating on a substrate at max heating 250°C and max pressure 70 bar. A stamp made of nickel or silicon. The substrate is heated and the stamp is pressed into the polymer. The resolution is up to 1 nm depending on the stamp.



SPIN150-NPP used for producing thin layers from dissolved materials (liquids) at room temperature. Layer thicknesses (nm-µm range) controlled by the rotation speed between 1-10000 rpm.

X-ray diffractometer

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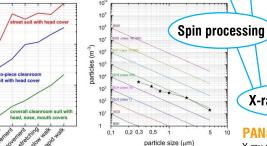
X-ray source : Cu K α , $\lambda = 1.5418$ Å.

Operating range: 10 - 70 °20, small-angle X-ray scattering possible too. Temperature: Room temperature, but temperature chamber available for lower and higher temperatures.

Humidity: Ambient, but humidity chamber available for different







PANalytical Xpert3 Powder

humidities. Sample amount: App. 10 mg